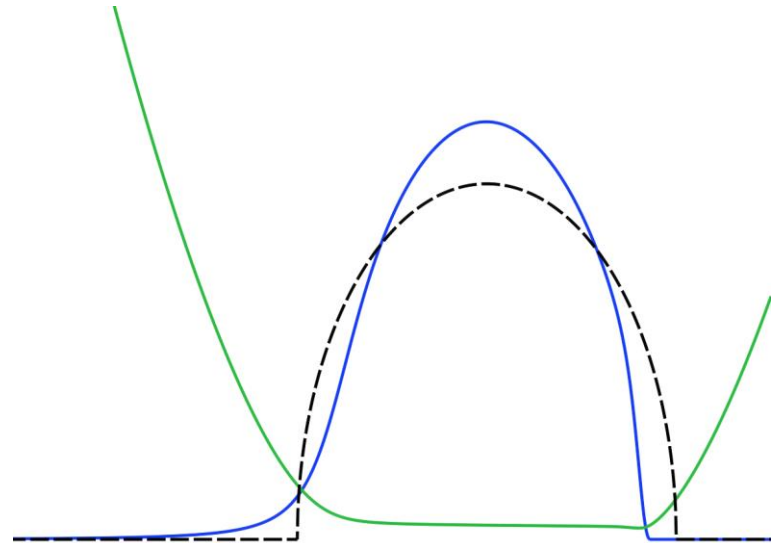


Simulating the layer thickness in roll-to-plate nanoimprint lithography

May 28, 2021

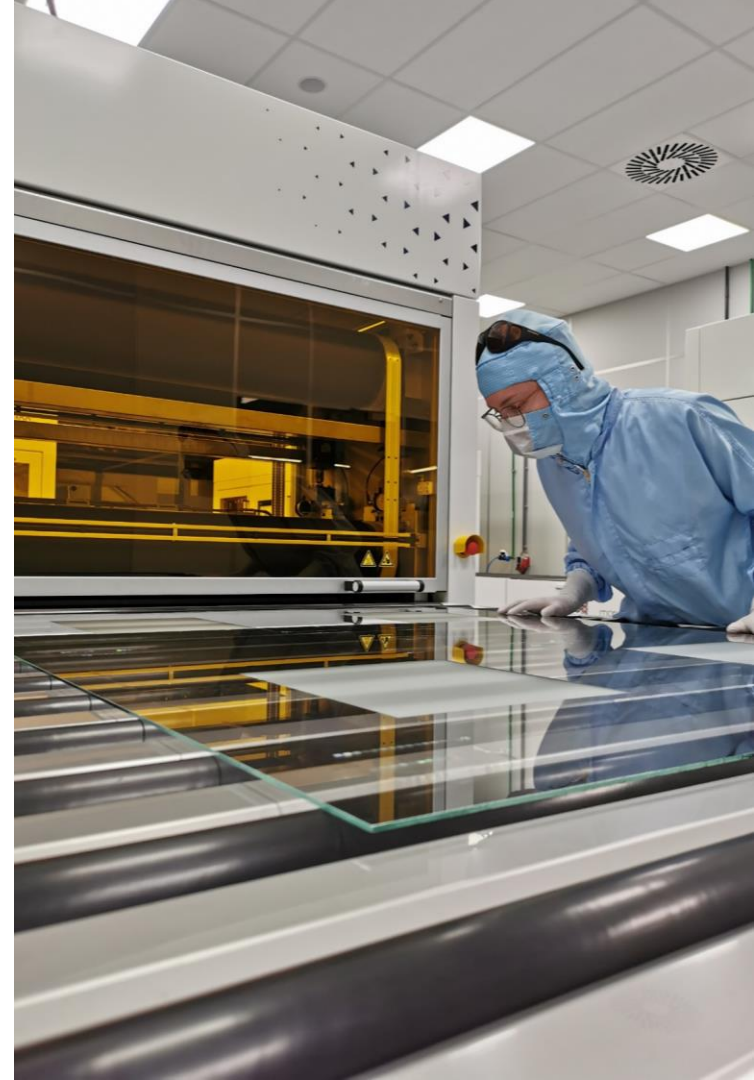
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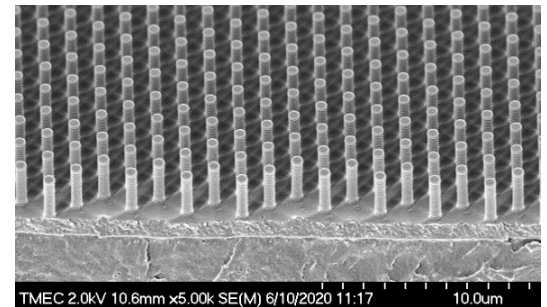
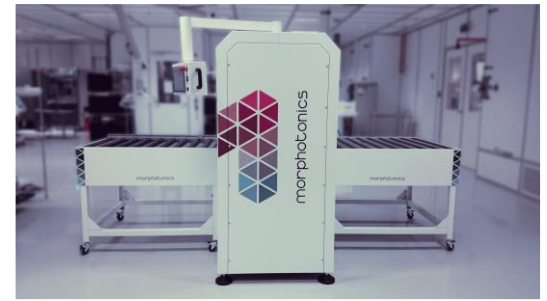
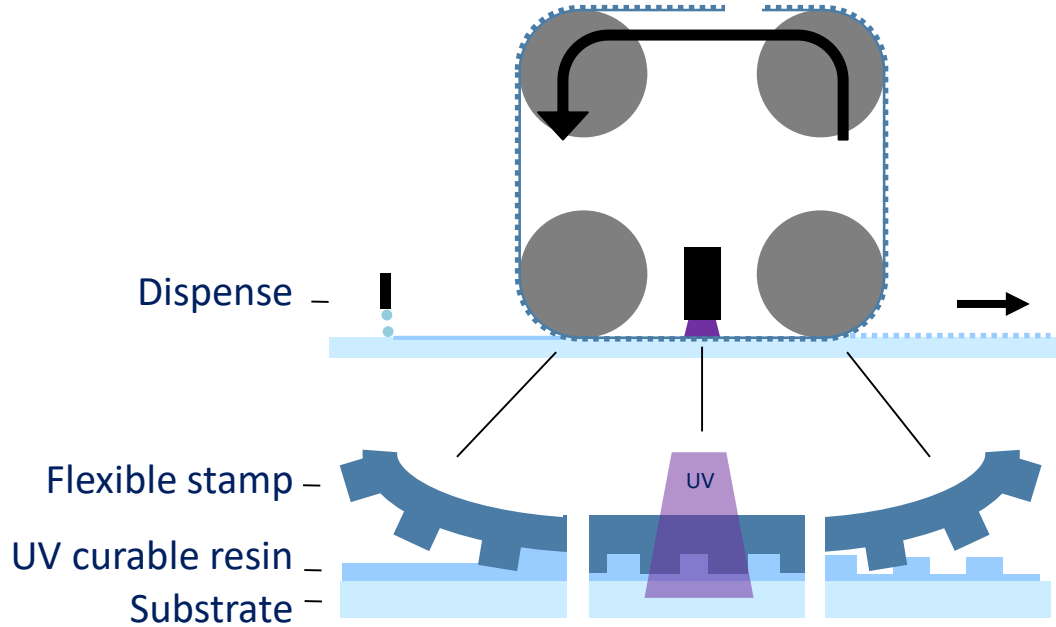


Morphotonics | about

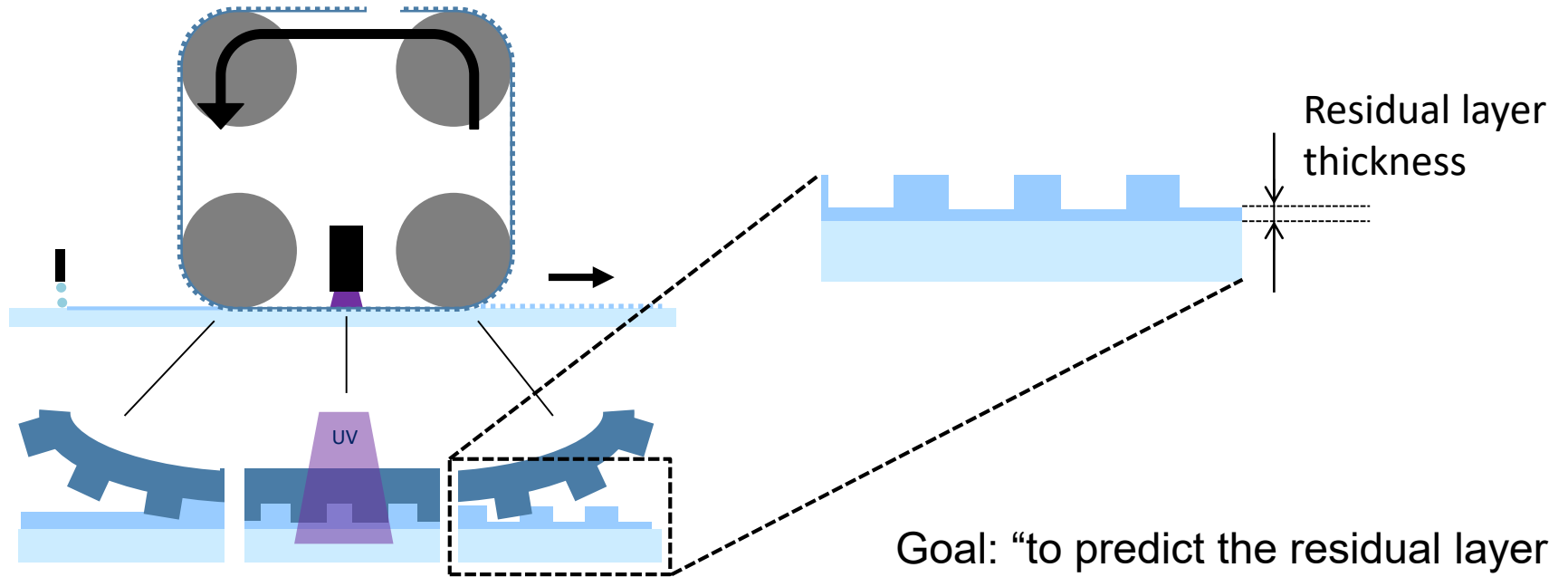
- **Technology** – large-area roll-to-plate micro- and nanoimprinting
 - Large-area: $>1 \text{ m}^2$
 - Textures: $500 \text{ }\mu\text{m}$ down to 50 nm
- **Business** – OEM supplier of equipment & consumables
 - Flexible stamps & UV curable resins



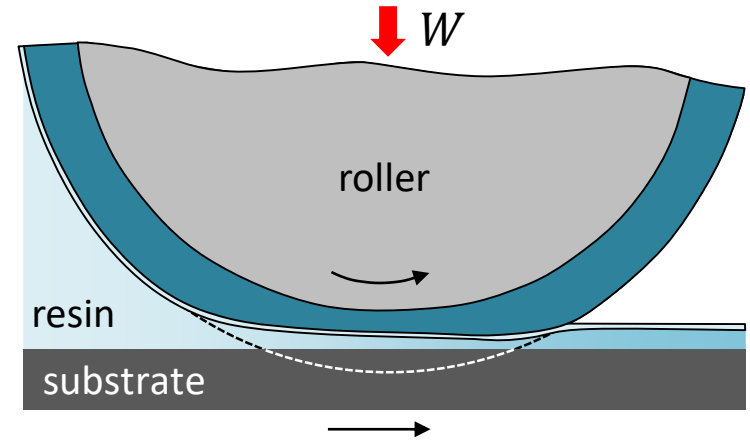
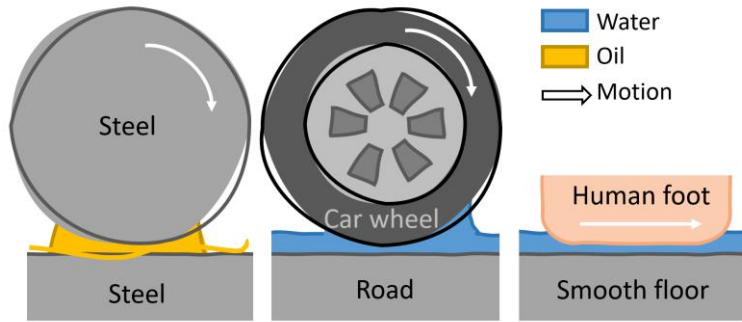
Morphotonics | R2P nanoimprinting



Modelling | research goal



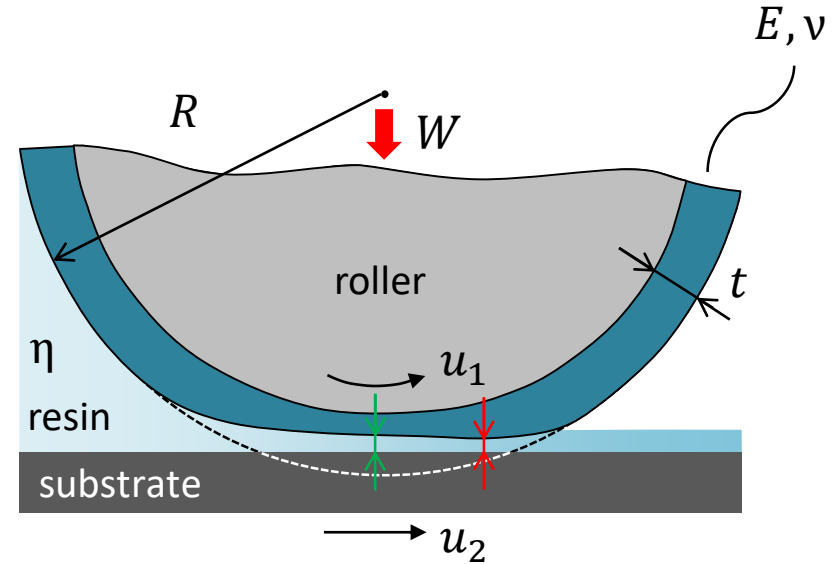
Modelling | Elasto-Hydrodynamic Lubrication (EHL)



“Systems in which the **elastic deformation** due to the pressure in the lubricating film is not negligible”

Modelling | relevant variables

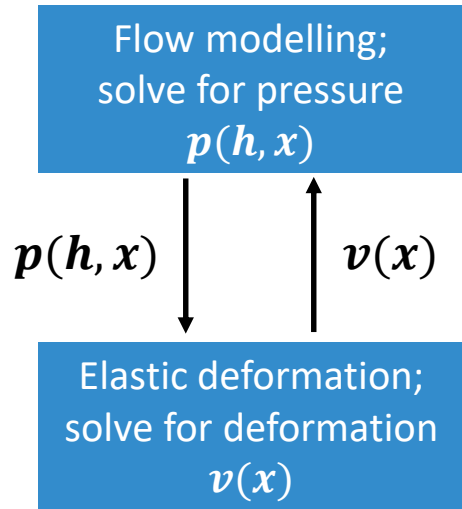
- Process variables
 - Load: W
 - Velocity: $U (= u_1 + u_2)$
- Material properties
 - Viscosity resin: η
 - Elastic modulus elastomer: E
 - Poisson ratio elastomer: ν
- Geometry
 - Roller radius: R
 - Elastomer thickness: t



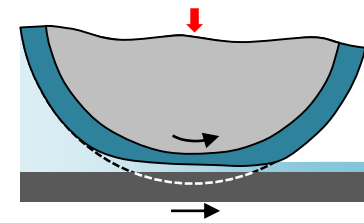
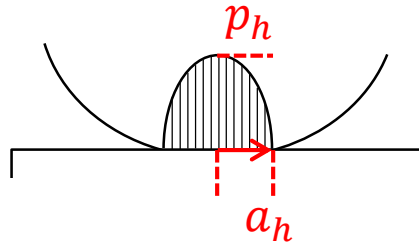
- Characteristic layer heights
 - Central layer height h_C
 - Minimum layer height h_M

Modelling | model set-up & result

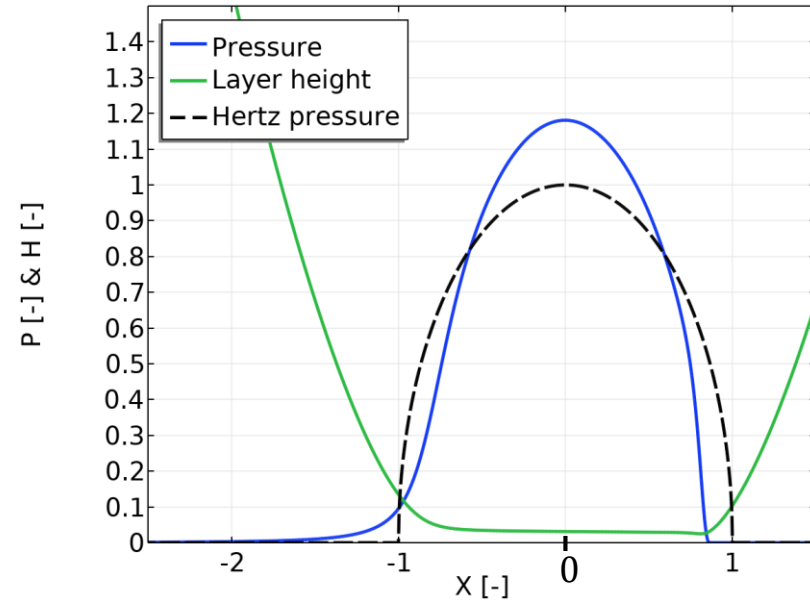
Multiphysics model



Hertzian scaling



Solution



Modelling | EHL literature

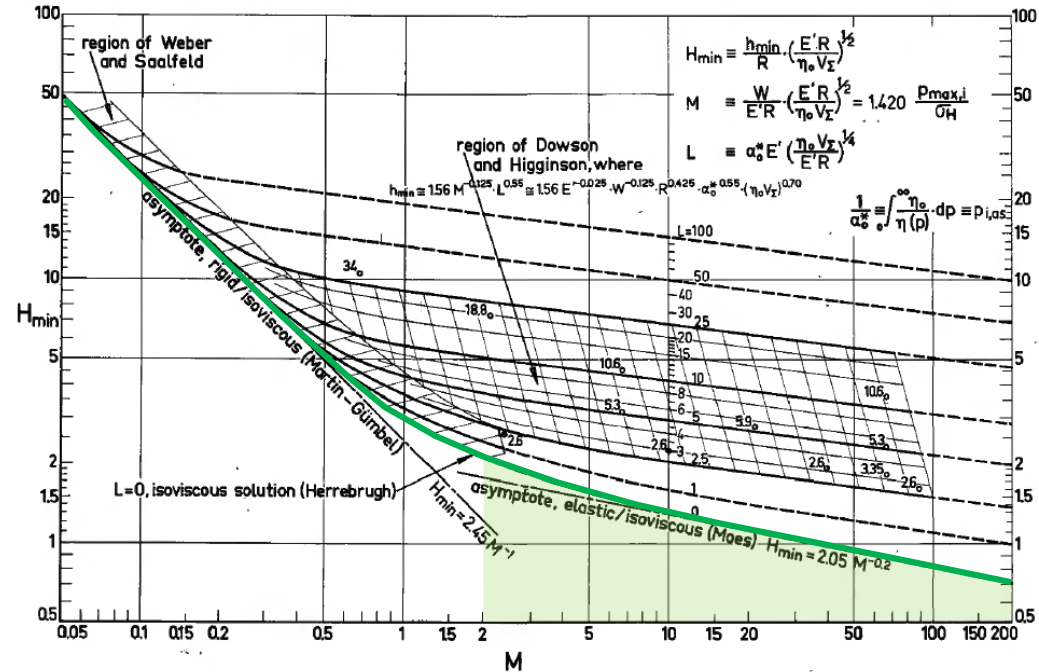
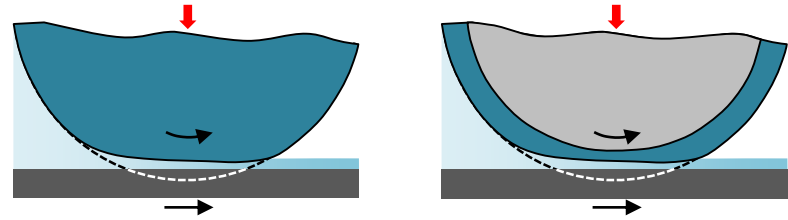
- Three dimensionless variables to describe all EHL solutions

– Load variable: $M = \frac{W}{E'R} \sqrt{\frac{E'R}{\eta U}}$

– Height variable: $H = \frac{h}{R} \sqrt{\frac{E'R}{\eta U}}$

– Viscosity variable: $L = \alpha E' \left(\frac{\eta U}{E'R}\right)^{\frac{1}{4}}$

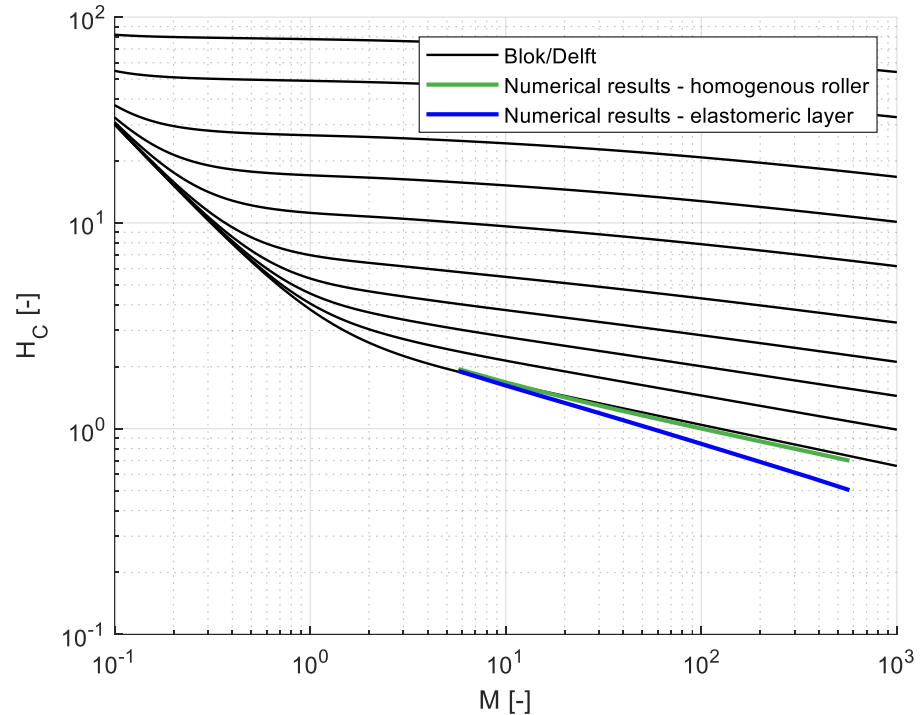
- Delft / Blok diagram (1966)



Modelling | numerical results

- Delft / Blok diagram
- Results model for
 - Homogeneous roller
 - Roller with elastomeric layer

$$M = \frac{W}{E'R} \sqrt{\frac{E'R}{\eta U}} \quad H = \frac{h}{R} \sqrt{\frac{E'R}{\eta U}}$$

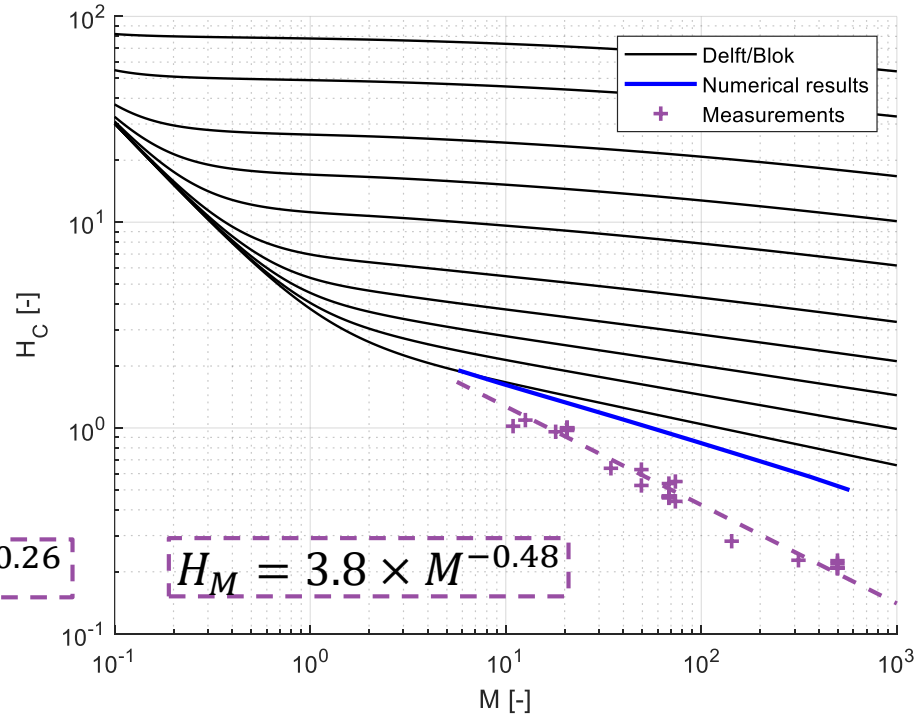


Experimental results | Delft / Blok diagram

- Variation of
 - Imprint equipment
 - Viscosity: η
 - Velocity: U
 - Load: W

$$M = \frac{W}{E'R} \sqrt{\frac{E'R}{\eta U}} \quad H = \frac{h}{R} \sqrt{\frac{E'R}{\eta U}}$$

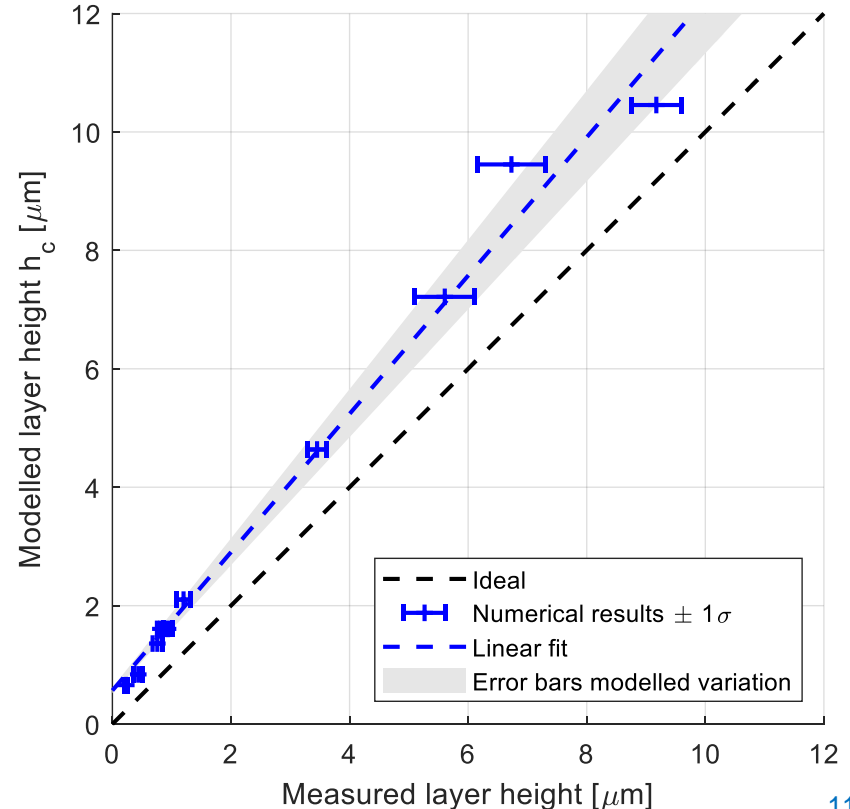
$$h_C = 3.8 \times (\eta UR)^{0.74} (W)^{-0.48} (E')^{-0.26}$$



Experimental results | layer height graph h_c

- Modelled variation over process parameters

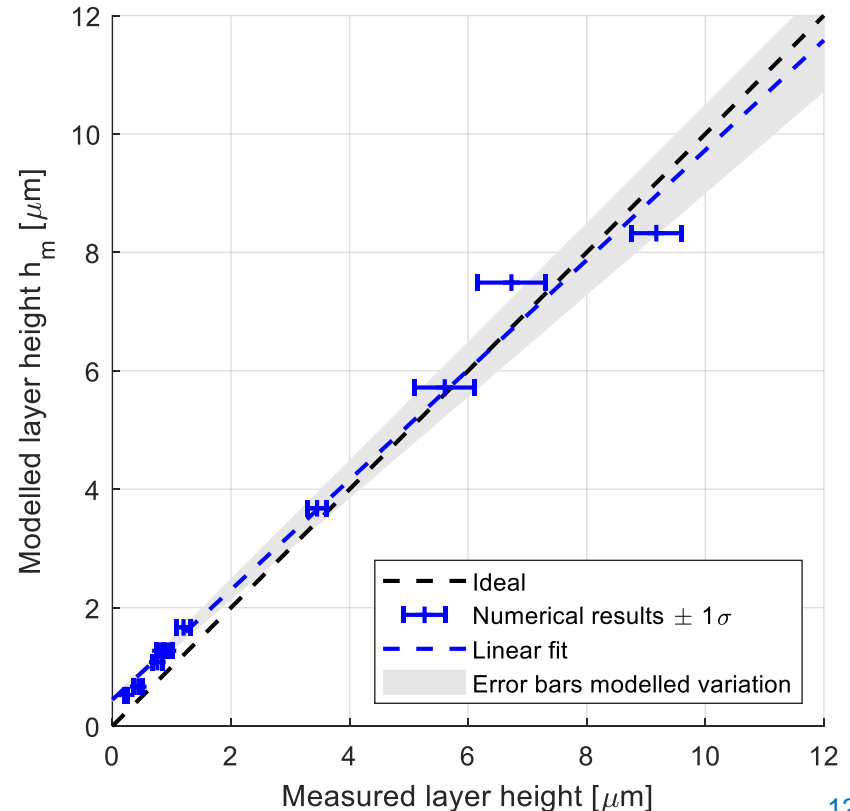
- Elastic modulus E : ± 3 Shore A
- Viscosity η : $\pm 5\%$
- Load W : $\pm 3\%$
- Elastomer thickness t : $\pm 0.5\%$
- Velocity U : $\pm 0.5\%$



Experimental results | layer height graph h_m

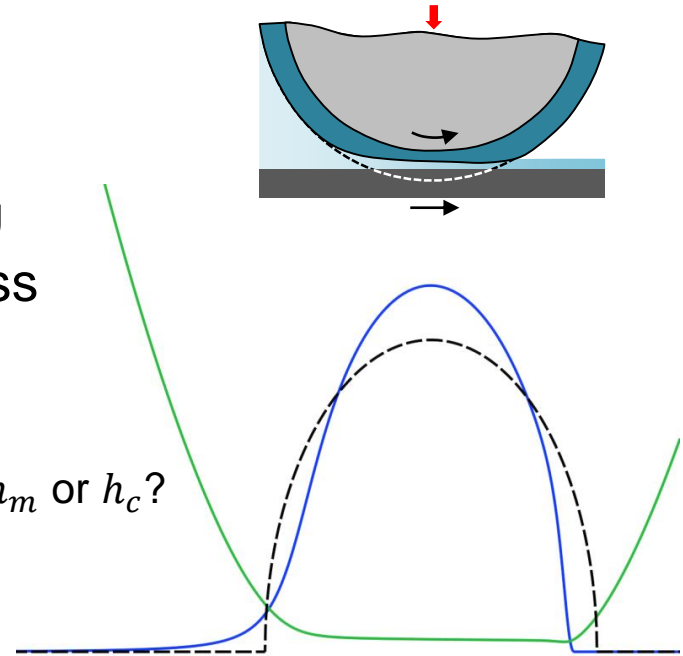
- Modelled variation over process parameters

- Elastic modulus E : ± 3 Shore A
- Viscosity η : $\pm 5\%$
- Load W : $\pm 3\%$
- Elastomer thickness t : $\pm 0.5\%$
- Velocity U : $\pm 0.5\%$



Conclusion & next steps

- Development of a numerical EHL model
 - Useful to study the layer thickness in R2P imprinting
- Empirical formula to predict the layer thickness
 - Based on EHL theory & dimensionless numbers
- Next steps
 - Determine the correct layer height from the model: h_m or h_c ?
 - Extension of the model
 - Flexible stamp
 - Textures



$$h_c = 3.8 \times (\eta UR)^{0.74} (W)^{-0.48} (E')^{-0.26}$$

This research was carried out
within the ELANIA RVO project

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